

# Radiation Design Considerations Using CMOS Logic

National Semiconductor  
Application Note 926  
Michael Maher  
January 1994



## INTRODUCTION

Today's rapidly changing global political climate is significantly impacting the military strategies of Free World countries. Important decisions are being made regarding each country's defense and military equipment needs. Regardless of these ongoing political changes, however, the threat of nuclear weaponry use remains a viable possibility. As long as a first-strike capability exists, radiation-hardened strategic and tactical systems will be designed.

In addition, radiation-resistance techniques increasingly focus toward space communication and exploration as more countries participate in the aerospace arena. As man ventures deeper and deeper into space, it is increasingly necessary to harden systems against space's natural radiation environments.

Designing and producing a radiation-hardened system is time extensive and financially expensive. Rather than meet premature demises due to inadequate radiation design, myriad precautions must be taken to ensure that satellites, for example, will survive their full life expectancies. Sometimes orbiting the Earth in excess of ten years, satellites incur very high costs due to emphasis on performance, reliability, and radiation resistance. Radiation hardening entire systems is a paramount concern.

Historically, radiation-sensitive space systems have been shielded in various materials. But because the payload pound-to-thrust cost ratio is also a critical concern, this approach is becoming unacceptable. Better methods, such as radiation-hardened ICs, are required to harden a system.

The severity of radiation exposure in space differs from that incurred in the tactical arena. While shielding space systems is very expensive, protection can be economical in tactical radiation environments, with notable exceptions being avionic systems, some tank systems, and shipboard equipment. While most failed systems in tactical equipment can be easily replaced, military conditions and requirements usually mandate that electronic systems remain fully functional throughout any nuclear event.

Lastly, today's commercial market requires limited radiation protection measures. Here shielding is generally the most viable and economical approach.

## INCORPORATING RADIATION DESIGN

Starting at the *conceptual stage* is the most efficient and cost-effective approach to designing a radiation-hardened system. This is where proper evaluation and selection of semiconductor technology and other factors occur, i.e., determining the extent of shielding, selecting viable existing technologies, and evaluating prototype futuristic IC technologies that will offer full availability by the time the system is in production.

Good decision making significantly lowers costs and increases the opportunity to keep a production schedule. Most critical at the conceptual stage is a thorough understanding of the system's mission relative to its potential radiation environments.

Depending on the mission, for example: satellite (commercial or military), tactical avionics system (nuclear event), or commercial application (nuclear power plant or medical), decisions can be made to utilize different types of components in different circuit applications.

## MISSION

Initial design decisions for space systems are based on whether it will be used in a military or commercial application. Radiation hardness requirements also differ if a satellite is in low orbit, high orbit, geosynchronous orbit, or polar orbit. Semiconductors in a satellite experience varying degrees of radiation degradation depending on whether they are resident on the satellite's exterior panels or are buried within its body. In space environments, major exposure comes from gamma ray irradiation and Single Event Phenomena (SEP).

Tactical systems (such as those in aircraft, shipboard, ground hardware, or equipment housed in missile silos or ground bunkers) each have distinct and unique radiation requirements. When designing a system, it must be known if that system must operate throughout a nuclear event or if it will be shut down until the event has passed. Systems subjected to a nuclear event must withstand gamma ray dose rate irradiation and neutron radiation.

The commercial environment has the easiest-to-accommodate radiation hardness levels. Although some equipment parts are exposed to severe hostile radiation environments, most parts can be protected with lead shielding or thick cement walls. Major concerns in the commercial environment stem from gamma ray total dose irradiation and neutron radiation.

## RADIATION ENVIRONMENTS

The more knowledgeable a designer is about radiation environments and their adverse affects, the greater the potential for proper technology selection and parts utilization for a cost effective, radiation-hardened design. System and circuit designers contend with five major radiation environments:

- Total Dose Ionization (Gamma Ray)
- Transient Irradiation (Dose Rate—Gamma Ray)
- Single Event Phenomena
- Neutron Radiation
- Electrical Magnetic Pulse (EMP)

EMP and neutron irradiation environments are not a concern for CMOS logic radiation design. Neutron radiation is not a factor as long as the fluence is under  $10^{13}$  neutron/cm<sup>2</sup>. At the present time, EMP environment is addressed at the system level, not by the component's technology.

## RADIATION DESIGN CONSIDERATIONS

Digital logic design, and CMOS technology in particular, provides inherent system hardness against radiation degradation. Beyond its high radiation resistance characteristics, CMOS logic (such as FACT<sup>™</sup> and FACT Quiet Series<sup>™</sup>)

FAST<sup>®</sup> and TRI-STATE<sup>®</sup> are registered trademarks of National Semiconductor Corporation. FACT<sup>™</sup> and FACT Quiet Series<sup>™</sup> are trademarks of National Semiconductor Corporation.

from National) offers the lowest power consumption, high advanced bipolar speeds, high packing density, and high noise immunity. Immune to neutron radiation and offering excellent total dose, transient (dose rate), and single event effects characteristics, CMOS logic is recommended for sockets previously occupied by other technologies. For example, while ECL is very hard in the total dose environment, it is susceptible in neutron and single event effects environments. The recessed oxide and walled emitters of advanced bipolar logic technology (FAST®, ALS) make it susceptible to neutron, total dose, dose rate, and Single Event Effects (SEE).

When designing a radiation-hardened CMOS system circuit, devices which use NAND gates are more tolerant than those with NOR gates. As NAND gates have p-MOSFETs in parallel with n-MOSFETs in series, both leakage current of the n-channel and increased threshold voltage of the p-channels are minimized. The NOR gate design has p-channel MOSFETs in series with n-channel MOSFETs in parallel connection and degrades more quickly in a total dose environment than NAND circuits.

As the number of inputs increases for a particular gate, radiation degradation accelerates as total dose levels increase. Depending on circuitry, CMOS device response may degrade, e.g., a flip-flop comprised of NAND gates has a different total dose degradation than one using inverters and transmission gates.

As the circuit's complexity increases, radiation degradation shifts from circuit parameter failure to circuit functionality radiation failure. Therefore, a microprocessor may fail functionality prior to circuit parameter failure. This also holds true for gate array designs. Each gate array has its own radiation response because of the internal metal connections to each cell; radiation hardness characteristics change with the design of each gate array's personalization.

To ensure the best RHA (Radiation Hardness Assurance) design, it is necessary to understand the complete radiation response of each component in the system circuit, e.g., what electrical parameters are affected by which radiation environments. This includes variable data and functionality (attribute) data to the level of radiation failure. Variable data as performed in a step-stress radiation approach permits observance of non-monotonic behavior for each electrical parameter's radiation response. For example, standby current of a non-hardened field oxide is non-linear and exhibits significant increases in value above its pre-radiation value. As 90% of all space projects require less than 100 krad(Si), radiation-hardened products such as FACT AC logic easily provide more than the required amount of resistance.

In space, the two most important radiation effects are total dose ionization (at a low dose rate) and single event effects. In the tactical environment, major concerns are transient (dose rate) radiation and neutron effects.

When designing a radiation-hardened system, guidelines must be established based on the system's mission and its required survivability. Following the conceptual phase of system design, proper components must be determined and selected for the investigative Engineering Development Phase. This critical design phase is often the most costly as component testing procedures include components, circuit board, systems assembly, and software documentation.

Following identification of the radiation environment, radiation test procedures must be established. A Hardness As-

surance Plan and Program must also be instituted. Establishing a Change Control Board ensures that any modifications to the circuit design do not impact the system's hardness assurance.

Once a system design is approved to radiation-hardness criteria, other documentation must be initiated that will prevent compromise to the established radiation hardness level. Written specifications must include radiation test conditions. Acceptance test procedures must be in place to ensure that components identified to HCI (Hardness Critical Items) specifications are properly tested. Lists must be established that identify those components and processes which are classified as HCI.

Part procurement drawings, assembly drawing schematics, and purchase orders require complete specifications of radiation requirements, including a *worst-case* circuit analysis. Worst-case analysis requires extensive system and circuit knowledge with respect to different radiation environments. Factors to consider include:

- Analysis of which circuit functions must operate through a particular radiation environment and those that would not
- The amount of available radiation shielding
- Selecting manufacturers with radiation-resistant components

One of the most costly efforts when radiation hardening a system is piece-part radiation testing. Here each component's radiation response is determined by different radiation environment simulators. Depending on the irradiation level, neutron testing can cost \$2,000 to \$4,000; for total dose testing, from \$2,500 to \$8,000, depending on the number of required radiation levels and the circuit's complexity.

#### SELECTION OF RHA COMPONENTS

Once a technology is selected, the next step is choosing Radiation Hardness Assured (RHA) components. Utilizing RHA devices reduces cost, improves reliability, and ensures the system's radiation hardware requirements. RHA component qualification does not guarantee these devices are impervious to adverse radiation effects, but that they have end-point electrical values which account for radiation-effects-generated responses.

If the system's manufacturer determines RHA acceptability via its own radiation testing program, the system's cost will significantly increase. In addition to the system manufacturer's involvement in comprehensive radiation testing, the OEM bears the cumbersome burden of scheduling and purchasing very costly radiation time at test facilities.

A better, significantly less expensive approach for OEMs who need RHA product is working with component manufacturers qualified to RHA.

Test results taken at varying radiation levels enable RHA vendors to specify irradiation limits for radiation-sensitive parameters. Care must be used in selecting RHA components. In general, RHA devices are qualified for neutron environment and total dose irradiation but are not specified for transient (Dose Rate) environment or Single Event Phenomena.

There are concerns associated with RHA components. A radiation design engineer must examine the vendor's data for any outstanding issues, annealing, lot-to-lot variation, wafer-to-wafer variation, and radiation test conditions. It is

important to select a semiconductor manufacturer that provides either the specified data or eliminates that particular concern. By choosing the correct technology and the correct component manufacturer, a radiation-hardened system can be produced with minimal cost, fewer components, and maximum survivability. The technology of choice to meet these radiation requirements is a CMOS with a thin epitaxial layer or silicon-on-insulator (SOS or SiO<sub>2</sub> process). National's FACT logic has been built on thin Epi since 1987.

## **TOTAL DOSE ENVIRONMENT AND DIGITAL LOGIC CMOS DESIGN**

### **A. Design Consideration**

Ionization radiation in a total dose environment affects the gate and field oxide of a CMOS semiconductor. When using CMOS technology, most vendors utilize the enhancement mode design of CMOS MOSFETs. This ensures the MOSFET will only turn ON when the proper threshold voltage is attained. When gamma rays strike the gate oxide that has an electrical field across it, photons generate electron-hole pairs. The electrons are swept out of the gate oxide leaving behind the holes (trapped charge). (Holes are actually positrons which have a positive charge with the mass of an electron.) This trapped charge causes threshold voltages to change. A positive trapped charge causes n-channel MOSFETs to approach depletion mode while p-channel MOSFETs are driven further into enhancement. Other generated charges (referred to as radiation interface states) cause the n-channel MOSFET threshold voltage to increase. P-channel MOSFETs are slightly affected by interface states. Trapped-positive charge and interface-state generation combine with subsequent annealing effects to constitute Time Dependent Effects (TDE) of total dose ionization.

Total dose radiation can degrade parameters to the point where a circuit's operation is detrimentally effected. To prevent this, designers must understand degradation, how device parameters are affected, and how to achieve a radiation-hardened design by properly applying the device in both the circuit and in the system.

The two major parametric concerns are leakage currents and propagation times. Depending on a vendor's CMOS processing, other parameters (such as  $V_{IL}$ ,  $V_{IH}$ ,  $V_{OL}$ ,  $V_{OH}$ ) may also change. With National's FACT logic, the only degraded parameters are  $I_{CC}$  (Standby Current) and  $I_{OZ}$  (TRI-STATE® leakage current). All other DC and AC parameters remain within published pre-rad limits.

### **B. Total Dose Testing**

To ensure a device's total dose resistance meets the required radiation hardness level, post-irradiation parametric values must be taken. Values can be ascertained only by component testing each device type. This is followed by careful evaluation of characterization data.

Total dose testing is performed using either a gamma or a low energy x-ray source. Gamma rays are usually generated by a Cobalt-60 or a Cesium-137 source. Another source of ionization radiation is an electron accelerator. Because most total dose testing is performed on finished product, the gamma rays or electron beam must have energy equal to or greater than 1 MeV at the oxide level.

Low-energy x-rays are the newest approach to total dose testing. Its advantage is testing during fabrication, rather than waiting for packaged die. Using low-energy x-rays, the

radiation hardness integrity of the gate oxide is analyzed as soon as polysilicon deposition and definition are completed. Because low-energy x-ray sources employ a photo-electric effect rather than the Compton Scattering effect, absorption rate and damage differ from values obtained via gamma ray sources and electron accelerators. The radiation damage ratio between low-energy x-ray and Cobalt-60 sources varies between 1.35 to 1.8. Total dose absorption from a low-energy x-ray source is expressed in rad(SiO<sub>2</sub>); gamma ray and electron accelerator sources express absorption in rad(Si). At 1.1 MeV, absorption is approximately equal for both silicon (Si) and silicon dioxide (SiO<sub>2</sub>). To prevent large errors and misleading information between the different sources, care must be taken and correlations made.

During total dose testing, device irradiation is under bias. In addition, radiation boards should be constructed to provide *worst case* radiation bias conditions. For CMOS logic devices, all inputs should be electrically connected to HIGH or LOW to prevent device oscillation or excess drawing of current; output pins may be either loaded or open-circuited. Test fixtures/boards must not distort the radiation field uniformity.

There are several methods of performing total dose testing: in-flux, in-situ, and remote testing. In-flux testing requires that devices be exposed to radiation while electrical parametric tests are conducted. In-situ testing requires that electrical parametric tests be made on the devices-under-test (DUT) while not being exposed to radiation. With remote testing, electrical parametric tests are performed on the devices which are physically removed from the exposure test chamber. When performing remote testing, it may be necessary to employ a mobile power supply to apply bias to the test fixture and DUT. This permits transfer of irradiated devices from the radiation area to another location for electrical parametric measurements while keeping devices under bias except for electrical parametric testing times.

Part of the ionization irradiation process is review of Time Dependent Effects (TDE). Annealing tests cause TDE changes in the electrical parameters (i.e., trapped charges during and after radiation exposure) that emulate the low dose rate environment of space. When considering TDE effects, additional testing is required, such as a standard irradiation test followed by a combination of additional irradiation and accelerated temperature anneal.

### **C. Characterization Data**

Characterization data is derived from thorough total dose radiation testing. For each particular device, it defines the radiation response to each radiation environment. Radiation-sensitive parameters are identified, and the radiation environments in which they pose problems are defined.

By using characterization data to better understand a function's response in each radiation environment, designers can tailor their approach to hardening the circuit and system's design. Data also identifies radiation-sensitive parameters, enabling designers to adjust system circuitry for minimal parametric degradation or for evaluating applicability of various vendors' products.

Characterization data is used to determine device design margins, and subsequently of the circuit design. However, the most important use of characterization data is establishment of parameter end point limits for device qualification.

For example, a system designer typically specifies a radiation level of 3 krad(Si) for devices to be used in the tactical environment. To eliminate lot acceptance testing, a design margin of 10x total dose level [30 krad(Si)] would have to be attained with an acceptable parametric-end-point limit and no functional failure of the device. *Figure 1* illustrates FACT characterization data. It shows a *worst-case* condition, depicting one of only two parameters for which FACT technology is radiation sensitive, i.e.,  $I_{CC}$  (TRI-STATE leakage current).  $I_{OZ}$  is only of concern if the device has TRI-STATE outputs.

Another example of total dose degradation is an increase in propagation time. By taking CMOS radiation characterization data and substituting these values in an AC circuit-timing simulator, a logic race or a contention condition can be detected.

Finally, design margin is an important concept in CMOS logic design and is used if a device function fails to meet or if it exceeds the radiation requirements of a specific project or application. Basically, design margin is a ratio of total dose radiation failure level versus specified total dose radiation failure level of the design. Design margins are determined by statistical analysis methods and can be applied as device, circuit, or system criteria. For CMOS logic, a design margin greater than 10 but less than 100 eliminates both lot acceptance tests and periodic radiation testing. A CMOS device possessing a design margin greater than 100 requires minimal radiation testing. If the CMOS device's design margin is less than 10, it must have lot acceptance testing and specified controls.

## TRANSIENT (DOSE RATE) RADIATION

### A. Design Consideration

Transient irradiation is primarily associated with a nuclear explosion and is a major concern for circuit and system designers of tactical equipment. Dose rate radiation is the amount of total dose irradiation given in specified time intervals.

This transient radiation pulse is expressed in rad(Si)/s or rad( $\text{SiO}_2$ )/s. In the real world, the nuclear event is over within milli-seconds, although it can continue up to a minute when delayed components are considered. In the dose rate simulated environment, the pulse width ranges from 3 ns to 10  $\mu\text{s}$  depending on the type of irradiating equipment being utilized. When a transient radiation pulse hits a device, the ionizing radiation is a function of time and is not constant. The affect of the dose rate pulse is generation of excess charge in a short period of time. This quantity of excess charge is dependent upon the total ionizing dose utilized. The concentration of these excess carriers is determined by the dose rate and carrier lifetime. Excess charge results when the ionizing pulse occurs at a faster rate than can be recombined. When a threshold level of excess charge is attained in a CMOS device, these radiation-induced effects can cause temporary effects or catastrophic failures:

- Upset (soft error)
- Latchup
- Junction burn-out

Other effects are short transient pulse on the output and saturated outputs which depend upon the amount of photocurrent (excess charge) generated and the output loading.

Upset of output data is a *soft* error since there is no permanent damage. Combinatorial circuits will upset then return to their original state. This type of upset generates a transient voltage at the output pin which might or might not affect the next IC device. Sequential logic circuits are the devices which upset and remain in this condition until the affected device is reset.

While logic upset may be acceptable for some projects, the dose rate threshold level is important as the designer must work around the upset condition. Latchup is a result of a sufficiently large quantity of radiation-induced photocurrent which initiates a parasitic Silicon-Controlled Rectifier (SCR). Once activated, this SCR acts as a low resistance path between ground and power supply. This condition usually leads to catastrophic failure, such as blown bond wires or metalization on the die.

Junction burnout is another catastrophic failure which occurs in the dose rate environment. This failure is generated when sufficiently large photocurrent is accumulated in the sensitive junction and cannot be distributed from this region quickly enough. As a result, thermal energy is increased to a level which causes junction burnout. For most technologies, the junction area is fairly large and heat can be dissipated. At very high dose rate levels, junction burnout becomes a major concern.

### B. Dose Rate Testing

Transient irradiation testing is performed by several approaches of which the primary testers are Linear Accelerator (LINAC) and Flash X-Ray. A third type of transient irradiator utilizes a laser approach. In its embryonic state, the laser technique has some limitations. The LINAC is used in the electron beam mode and is capable of providing both a narrow pulse and wide pulse ranging from 3 ns to 10  $\mu\text{s}$  pulse widths; the pulse must have an energy level greater than 10 MeV. The Flash X-Ray (FXR) machine is limited to narrow pulse widths and is operated in the photon mode. For both approaches, the total dose is generally limited to 500 rad(Si)  $\pm 200$ .

When considering upset testing, an analysis of the circuit's topology should be done prior to testing. This eliminates unnecessary testing of certain test paths and minimizes the amount of required testing. *Worst case* test conditions for upset utilize the lowest permitted power supply voltage for the system's application and a wide dose rate pulse of greater than 200 ns. All modes of operation should be investigated and tested, i.e., TRI-STATE, shift-left, etc. Static and dynamic operations of the device must be evaluated for dose rate sensitivity. If a clock signal is associated with the DUT, then the relative position of the radiation pulse with respect to the CLOCK signal's transition edge becomes an important factor. Upset levels are affected by the internal inductance of the device and associated test circuitry. Care must be taken to minimize parasitic inductance since this will give upset levels that are lower than the device's true upset level. To compensate for this parasitic inductance, a capacitor can be added to the test circuit.

*Worst case* test conditions for Dose Rate latchup testing are highest utilized power supply voltage, highest anticipated temperature, and the shortest dose rate pulse width. Investigating existence of latchup *windows* is also recommended. Latchup *windows* are regions of dose rate levels where the device will latchup; areas below or above

this region will not latchup. Performing four dose rate levels per decade is acceptable to determine latchup *windows*.

When performing dose rate testing for upset, latchup, and burnout, it is important to perform both functional and parametric testing of the DUT after each test. This determines if any of the previously-mentioned effects occurred or if any parametric degraded as a result of total dose.

### **C. Dose Rate Characterization Data**

When the circuit designer has dose rate test data, decisions can be made on latchup prevention and upset correction methodologies. Upset threshold levels, determined by dose rate testing, will assist in selection of parts and design margin analysis. From the dose rate testing, it is necessary to determine if the device has pulse width or current sensitivity.

If the device's dose rate upset response indicates that it is a function of pulse width, then an extreme pulse width value must be used in radiation design calculations and transient irradiation tests. Otherwise, the device's dose rate response is dependent upon current and any dose rate pulse width less than the value can be employed.

When a transient pulse is detected by the system's nuclear event detector (NED), data can be stored in radiation-hardened memory and recovered at a later time when the nuclear event has passed or dissipated. Another technique is disallowing present data of a transient irradiation, and recycling the computer for data retransmission before the nuclear event. Still other approaches are used when operation through a nuclear event is necessary.

The best method is utilization of devices that are very insensitive to upset or that demonstrate high upset levels. Avoid the use of CMOS memory devices which do not otherwise employ an internal split or partitioning of the power supply rail; otherwise, rail span collapse will occur. Rail span collapse is the reduction of power supply voltage below a value due to the induced dose rate photocurrent. When this occurs, the memory cells farthest from the power supply bond pad will be the easiest to upset.

Other approaches use circuit schemes. This requires additional components to compensate for photocurrent generated by transient radiation, such as employment of a differential amplifier to reject common-mode primary currents or the use of filter circuits to prevent radiation-induced voltage transients from propagating to the circuit's outputs. The increase in components has several associated penalties:

- Increased cost
- Increased board area
- Decreased circuit speed

Choosing the appropriate radiation-resistant products minimizes these penalties, providing additional upset protection.

Evaluation of characterization data determines the approach to be used. Burnout can be either metal lines (due to a metal defect or the current density for that particular line or bond wire being exceeded) or junction burnout. To prevent burnout, a current-limiting resistor isolates the power supply from the device, thereby limiting the radiation-induced photocurrent. This resistor also assists in preventing latchup. The penalty paid for using this resistor is higher power consumption and decreased device speed.

One approach to latchup elimination is using dielectric isolation devices (CMOS/SOS, CMOS/SOI) or CMOS-Epi product.

CMOS/SOS and CMOS/SOI products are inherently latchup immune. CMOS/SOS is somewhat costly; CMOS/SOI is a new product with a minimum track record. CMOS-Epi has the best solution when cost and performance are considered. However, care must be exercised when selecting CMOS-Epi parts since thick epitaxial layers greater than 10  $\mu\text{m}$  should be avoided and the substrate and Epi must have low resistivities as permitted by the process technology. When using CMOS-bulk devices, the substrate should be gold lapped or neutron irradiated in order to reduce the minority carrier lifetime of the substrate. This will reduce the combined gains of the parasitic bipolar transistors that constitute the parasitic SCR to much less than one (gain  $\ll 1$ ).

## **SINGLE EVENT EFFECTS (SEE) AND CMOS DIGITAL LOGIC DESIGN**

### **A. Design Considerations**

Single Event Effects (SEE) are predominantly associated with trapped radiation in space. They were observed in the early 1960s, but were not of concern until the latter half of the 1970s. As technology evolved to decreased geometries, feature sizes, and gate oxide volume as well as increased device speed, the energy required for gate switching was reduced. As a result, low energies (0.5 pico joules) can now switch device gates, making SEE-charged particles an important radiation environment.

SEE hardness design is dependent on mission requirements and circuit application of the device. Mission requirements affecting SEE design include orbit placement, time duration in space, and orbit inclination. Single Event Phenomena (SEP) is generated by three charged particles: alpha, protons, and heavy ions.

- The alpha particle—the weakest of these particles in causing SEE problems—causes upset in sequential logic or memory devices. Thorium, a radioactive material used in ceramic packages, is a source for alpha particles.
- High-energy protons originate in the Van Allen Belts or by solar flares. Only those protons having energy greater than 10 MeV will cause a single event problem.
- Heavy ions are also caused by solar flares and galactic cosmic rays.

The detrimental results of SEE on electronic systems include transients, soft errors, and permanent damage. Single Event transient spikes are generally associated with combinatorial logic circuits. The transient spike resulting from a Single Event strike has a short time duration, but could contain sufficient energy to cause a subsequent sequential or combinatorial logic input to change. While combinatorial logic outputs have transient upset, the inputs will force the output to its original state. Soft errors are temporary Single Event upsets and are defined as *bit flips*.

Latchup is the major permanent damage caused by SEP. This and other effects, such as funnel effect, result when a high-energy charged particle passes through a sensitive area. As the charged particle passes through the sensitive volume, it deposits energy along its path. The rate of energy loss in the material is Linear Energy Transfer (LET). This energy loss generates a plasma of electron-hole pairs. If

this plasma occurs in a depletion area of the sensitive region, induced current is generated. This induced current is primarily collected from the depletion region and the funnel region. It consists of:

- *Drift*: Generated in the depletion region and part of the prompt portion of the induced current.
- *Funnel Charge*: Generated in the funnel region, located below the depletion area of the sensitive area. The funnel region results from instantaneous distortion of electrical fields, deep into the silicon. The current caused by the funneling effect is greater than the drift component and is quickly drawn back into the sensitive region's contact.
- *Diffusion*: The delayed portion of the total induced SEE current. The diffusion region is located below the funnel region. *Figure 2* shows the composite drawing of the induced SEE current.

Induced current is a function of the circuit's parameter, the voltage applied at the sensitive node, and node capacitance. The amount of charge required to generate a change of state in a memory cell or sequential logic device is defined as the *critical* charge. Associated with the *critical* charge are the sensitive nodes of an IC device. Sensitive nodes are the reversed-biased nodes; e.g., the OFF drains of the p- and n-channels of a memory cell. The collected charge at these sensitive nodes causes a voltage transient to be developed and applied to other cross-coupled inverters of the memory cell or sequential logic device that generates the change of state at the output of the device.

Latchup is another major concern in the Single Event Effects environment and can affect devices manufactured on CMOS, bipolar, and ECL processes. Because of heavy ions, latchup in CMOS technologies is generally associated with a CMOS bulk technology or with CMOS devices fabricated on a thick epitaxial (Epi) substrate. While similar to Transient (Dose Rate), SEE latchup is generated by heavy ions. Since SEE latchup usually has catastrophic results, designers must carefully select components that will be impervious to a single particle strike. It is therefore necessary to select devices which are fabricated with guard rings, built on a very thin Epi, or that utilize dielectrically-isolated CMOS technologies (SOS, SOI). National's FACT product is manufactured on a very thin epitaxial layer. At extremely high LET levels, FACT remains immune to latchup from heavy ions.

### B. Single Event Testing

There are several sources for performing Single Event testing. The two major sources are the cyclotron machine and Van de Graaff accelerators. The cyclotron apparatus provides maximum capability of providing a variety of heavy ion species at different magnitudes of energies. As a result, a wide level of penetration depths into the device can be attained. The usual maximum ion energy level approximates 2 MeV/nucleon for this radiation source. Using the cyclotron is expensive and time consuming. Some of the problems associated with these machines are beam diagnostics, e.g., the amount of time it takes to change ion species or ion energies [3].

The second source for testing SEP is the Tandem Van de Graaff Generator. This testing approach is less expensive than the cyclotron. A limiting factor, however, is its usable energy, i.e., the higher Z ion species' range is limited. It is

much easier to change ion species in a short time. Additionally, the Van de Graaff machine can determine low LET thresholds of sensitive devices where lower energy, lower Z ions of continuously variable energies are needed [3].

When performing SEP testing, the company requesting this test supplies support personnel, DUT boards, a device exerciser, and any additional support equipment such as data reduction equipment or diagnostic equipment. The user must also select the ion species and LET threshold. The user will determine the test philosophy and prepare a test plan based upon the selection of the radiation source. When using the cyclotron or Van de Graaff machine, DUTs must be uniddled. The user is responsible for all hardware operation and a number of dry runs may have to be performed before all is acceptable. Test facility personnel will perform beam uniformity measurements, flux measurement, energy measurements, and other diagnostic activity in order to ensure beam accuracy. Facility personnel are responsible for all other activities associated with the radiation source, such as beam dosimetry.

### C. Characterization Data

It is important to know what constitutes characterization data for Single Effect design. By using SEE characterization data, circuit simulation is a proven means to ensure that the circuit and system will be hardened to this environment. The circuit designer must obtain specific information from the vendor concerning SEE testing, the different temperatures under which testing was performed, the range of angle of incidence, dimension of the sensitive volume, feature size and process information, cross-sectional area, the LET values for upset and for latchup, and the critical charge value that causes inversion of output data. Employing this data in an SEE simulation program will provide the designer with additional data, such as the particle count and the minimum LET energy necessary to generate the critical charge within the specified volume that will cause upset. Data obtained through the simulation is then compared and validated with the vendor's test data. Performing several more simulations and using several different values of critical charge, a plot of critical charge versus error rate can be generated. This type of plot is particular to each memory cell device or other sequential logic device being utilized in the system's design.

In memory cells, the approach for increasing the SEU hardness level is use of polysilicon *feedback* resistors. The resistor decouples the sensitive nodes of the *off* n- and p-channel devices. Other approaches employ circuit diodes and active devices in the feedback. This is done by increasing the RC time of the feedback loop, allowing more time for the circuit to recover from SEU high and increasing the charge required on the gate to cause a *bit-flip*. When using polysilicon cross-coupled resistors, temperature becomes a factor as the negative co-efficient of these resistors increases the resistance when the device is exposed to decreased temperatures. As a result, the memory circuit becomes slower at colder temperatures.

Other sequential devices such as data latches require additional internal circuitry rather than resistors, thus adding to chip size. Resistors also increase power consumption and decrease device speed.

From a system perspective, SEP can be addressed in several ways. Ground Control personnel maintain a circumvention scheme for shutting the system down when under im-

mediate threat. Another method is utilizing circuit redundancy; this is founded on the precept that the probability of the same two circuits being hit by an ion at the same time is very low. Use of Error Detection and Correction (EDAC) is another approach, as is use of two-level parity code.

FACT logic is built on a CMOS-Epi process which utilizes a very thin Epi and low substrate resistivity. The result is a product line which truncates the funnel effect, limits the amount of charge collection, and is latchup immune to LET  $\geq 120$  MeV/mg/cm<sup>2</sup>. Recently, several FACT device types were tested for SEU and all devices had an LET  $\geq 40$  MeV/mg/cm<sup>2</sup> and a cross-sectional area  $\geq 2 \times 10^{-5}$ .

#### USING FACT LOGIC

The system's mission and its associated radiation environment direct the testing for obtaining radiation design data. This knowledge assists the designer in making the proper component selection. This same radiation characterization data defines the restrictive conditions for the circuitry's design and the necessary design trade-offs.

When possible, CMOS-Epi product should be used in radiation-hardened design. Only where required or imperative should radiation-hardness-dedicated CMOS devices be employed. This reduces system cost. National's FACT logic family is the most radiation-resistant ACMOS logic family available to Military/Aerospace designers and is the Advanced CMOS logic family of choice for radiation applications. Its tolerance exceeds that of other logic families. As long as the neutron fluence is under  $10^{13}$  n/cm<sup>2</sup>; neutron radiation does not affect the FACT product line.

FACT logic provides high radiation resistance in all environments. For total ionization dose, its 100 krad(Si) capability provides the same post-irradiation drive as its preradiation value with propagation time deltas of less than 0.5 ns at high dose rate levels. At lower space dose rates, FACT logic is superior to other logic families. FACT is resistant to total ionization radiation because of its thin gate oxide and low temperature processing.

FACT's Epi (Epitaxial Layer), p-well design, and low-resistivity substrate provide inherent latchup immunity and high upset tolerance in both Dose Rate and Single Event Phenomena Environments. Because of this technology, fewer parts are needed to provide the required radiation hardness level. This minimizes the use of circumvention schemes or other conventional radiation hardening techniques. Use of FACT product reduces weight, board space, and is a very cost effective approach to radiation-hardened system design.

#### NATIONAL'S LOGIC TEST PHILOSOPHY

National Semiconductor offers a solution that reduces the need for extensive shielding measures while maintaining cost effectiveness. By testing inherently radiation-resistant standard devices, National provides products that offer you:

- Custom testing as outlined in customer SCDs (Source Control Drawings)
- Guaranteed specifications for reliable radiation designs
- Cost effectiveness
- Timely delivery

Through National's Mil/Aero Logic Radiation Program, products are fully qualified with respect to different radiation environments. Complete Total Dose radiation data is supplied with each customer order, certifying radiation resistance to the level specified in each SCD.

National recognizes that radiation resistance needs differ within tactical and space environments. Our radiation resistance program is flexible to individually address your requirements, according to your radiation and processing needs. Several process flows are available, including Level S, Level B, Standard Military Drawings (SMDs), MIL-STD-883, and Source Control Drawings (SCDs).

FACT products are manufactured in a DESC-certified JAN Class S wafer fabrication facility. All of the company's logic radiation research and development is performed in National's South Portland, Maine, Radiation Effects Laboratory (REL). This REL is:

- Certified by the National Institute of Standards and Technology (NIST).
- Licensed by the Nuclear Regulatory Commission (NRC) to handle neutron-irradiated material. This REL capability permits testing product for both total dose and neutron irradiation. National currently is contracting Sandia National Labs to perform neutron irradiation.
- Certified by the Defense Electronic Supply Center (DESC) for Lab Suitability. This certification signifies that our REL has met all government requirements to perform total dose testing. This certification is one of only two presently granted by DESC.

Lab Suitability certification denotes that testing performed at National's South Portland REL facility and the data generated are fully recognized and acceptable by all government agencies, their contractors, and subcontractors. This qualifies the south Portland REL to support JAN Class S RHA programs for FACT product as well as for any customer-requested testing that requires total dose data from a DESC-certified laboratory.

REL research includes evaluation of National's logic families as well as any other products requested by customers.

National is in the process of qualifying FACT devices to RHA (Radiation Hardness Assurance) standards, with approval expected by mid-year, 1991. At that time, FACT AC JAN Class S and B devices will bear an "R" designation as part of the JM38510 Slash Sheet number, denoting RHA certification to 100 krad(Si); FACT ACT a "D" as part of the SMD number, signifying RHA certification to 10 krad(Si). National will also be submitting data on its FACT Quiet Series and FACT FCT SMD products, also for RHA certification to 10 krad(Si), or a "D" designator.

**Note:** This text was used as the basis for an article published in the January, 1991, edition of the German magazine *Design & Elektronik*, "Strahlungsfeste Designs mit CMOS-Logik."

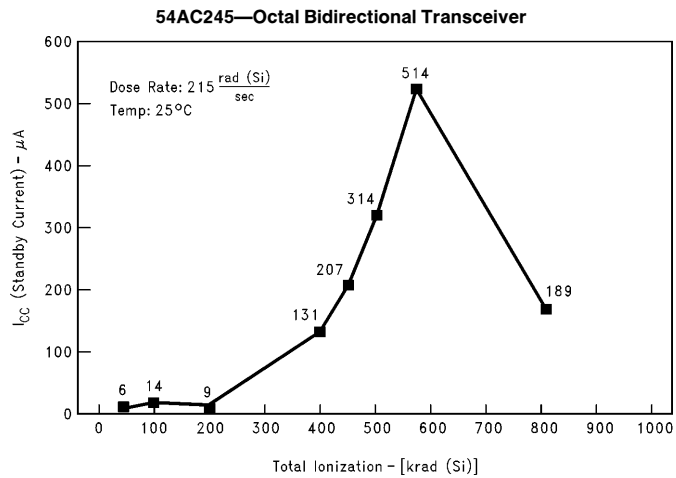
**TABLE I. Example of Radiation Characterization Data for I<sub>CC</sub> (Standby Current)**

Part Type: 54AC00 Quad 2-Input NAND Gate

Dose Rate: 142 rad(Si)/sec

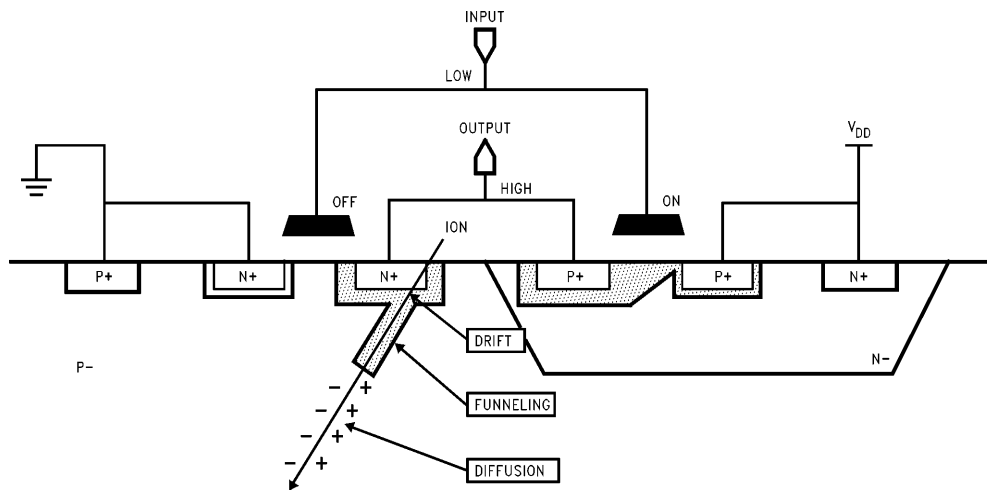
Parameter: I<sub>CC</sub>

Dose Level [krad(Si)]	Minimum Value (μA)	Mean Value (μA)	Maximum Value (μA)
Pre-radiation	0.019	0.047	0.340
5	0.413	0.616	1.024
10	7.870	13.631	22.907
50	43.033	74.330	136.920
80	43.033	61.289	105.630
100	11.736	43.033	74.329
150	11.736	37.817	74.329



**FIGURE 1.  $I_{CC}$  (Standby Current) Versus Total Dose**

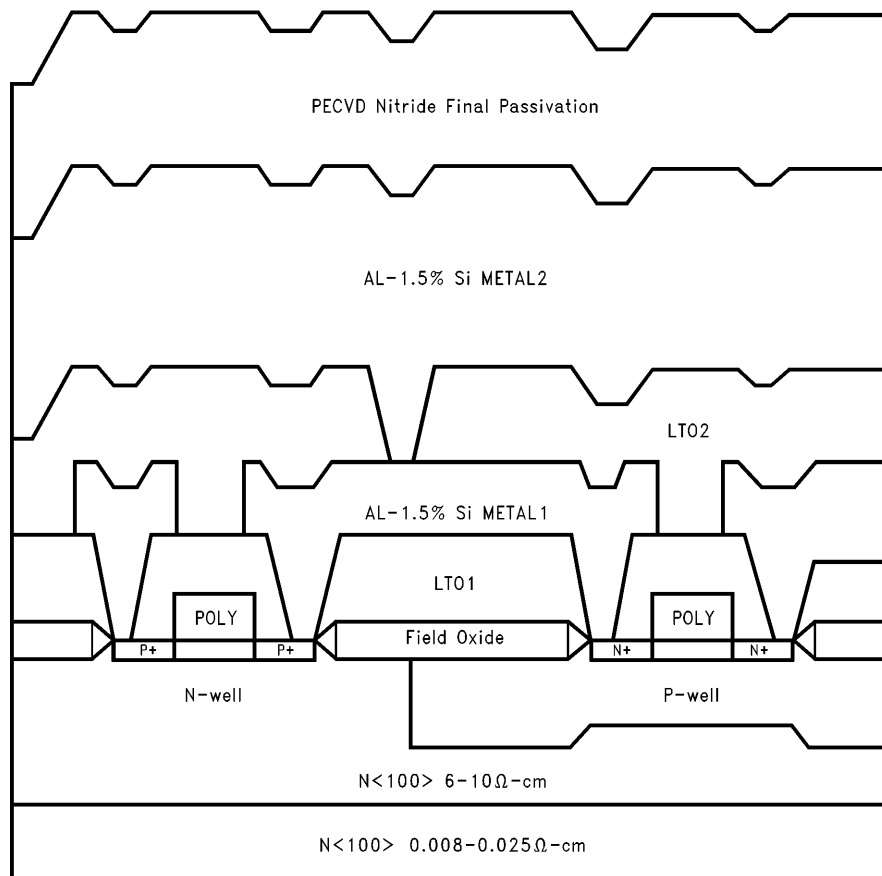
TL/F/11650-1



**FIGURE 2. Single Event Effects Generated Currents [7]**

TL/F/11650-2





TL/F/11650-3

**FIGURE 3. Final Processed Cross-Section of the FACT Technology**

**LIFE SUPPORT POLICY**

NATIONAL'S PRODUCTS ARE NOT AUTHORIZED FOR USE AS CRITICAL COMPONENTS IN LIFE SUPPORT DEVICES OR SYSTEMS WITHOUT THE EXPRESS WRITTEN APPROVAL OF THE PRESIDENT OF NATIONAL SEMICONDUCTOR CORPORATION. As used herein:

1. Life support devices or systems are devices or systems which, (a) are intended for surgical implant into the body, or (b) support or sustain life, and whose failure to perform, when properly used in accordance with instructions for use provided in the labeling, can be reasonably expected to result in a significant injury to the user.
2. A critical component is any component of a life support device or system whose failure to perform can be reasonably expected to cause the failure of the life support device or system, or to affect its safety or effectiveness.



**National Semiconductor Corporation**  
2900 Semiconductor Drive  
P.O. Box 58090  
Santa Clara, CA 95052-8090  
Tel: (408) 272-9959  
TWX: (910) 339-9240

**National Semiconductor GmbH**  
Livny-Gargan-Str. 10  
D-82256 Fürstenfeldbruck  
Germany  
Tel: (81-41) 35-0  
Telex: 527849  
Fax: (81-41) 35-1

**National Semiconductor Japan Ltd.**  
Sumitomo Chemical  
Engineering Center  
Bldg. 7F  
1-7-1, Nakase, Mihama-Ku  
Chiba-City,  
Chiba Prefecture 261  
Tel: (043) 299-2300  
Fax: (043) 299-2500

**National Semiconductor Hong Kong Ltd.**  
13th Floor, Straight Block,  
Ocean Centre, 5 Canton Rd.  
Tsimshatsui, Kowloon  
Hong Kong  
Tel: (852) 2737-1600  
Fax: (852) 2736-9960

**National Semicondutores Do Brazil Ltda.**  
Rue Deputado Lacorda Franco  
120-3A  
Sao Paulo-SP  
Brazil 05418-000  
Tel: (55-11) 212-5066  
Telex: 391-1131931 NSBR BR  
Fax: (55-11) 212-1181

**National Semiconductor (Australia) Pty, Ltd.**  
Building 16  
Business Park Drive  
Monash Business Park  
Nottingham, Melbourne  
Victoria 3168 Australia  
Tel: (3) 558-9999  
Fax: (3) 558-9998

National does not assume any responsibility for use of any circuitry described, no circuit patent licenses are implied and National reserves the right at any time without notice to change said circuitry and specifications.